

SYSTEM AND METHOD FOR THE REAL TIME DETERMINATION OF THE IN SITU
EMISSIONIVITY OF A WORKPIECE DURING PROCESSING

ABSTRACT OF THE DISCLOSURE

A system (10) and method for determining the reflectivity of a workpiece (W) during processing in a heating chamber (74) of a thermal processing apparatus (22). The system first determines directly the reflectivity of the workpiece outside of the heating chamber (74) of the thermal processing apparatus, and then determines the reflectivity of the workpiece during processing within the heating chamber (74) of the thermal processing apparatus (22) by correlating the *ex situ* wafer reflectivity with the intensity of the radiation reflected from the wafer within the heating chamber.

Figure 1